

# FreePDK3

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## Design Rule Manual

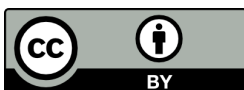
**Revision:** 1.0

**Process Node:** 3nm

**Release Date:** August 30, 2021

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# 1.Layer Information

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## 1.1 Front-End-of-Line (FEOL) Layers

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| Layer | Description                 | Lithography | Patterning |
|-------|-----------------------------|-------------|------------|
| NW    | N – Well                    | 193i        | SE         |
| BPR   | Buried Power Rail           | 193i        | LE2        |
| VBPR  | Via connecting BPR to M0A   | 193i        | LE2        |
| ACT   | Active for Nanosheet Layers | 193i        | SADP       |
| GATE  | Gate Metal                  | EUV         | SADP       |
| GCUT  | Gate Cut Metal              | 193i        | SPT        |
| DUMMY | Dummy Poly                  | EUV         | SAQP       |
| NIM   | N - implant                 | 193i        | SE         |
| PIM   | P - implant                 | 193i        | SE         |

## 1.2 Middle-of-Line (MOL) Layers

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| Layer | Description                  | Lithography | Patterning |
|-------|------------------------------|-------------|------------|
| M0A   | Metal M0A interconnect layer | EUV         | DPT        |
| V0A   | Via connecting M0A to M0B    | EUV         | DPT        |
| GCON  | Gate interconnect layer      | EUV         | DPT        |
| M0B   | Metal M0B interconnect layer | EUV         | SALELE     |
| V0B   | Via connecting M0B to M1     | EUV         | DPT        |

## 1.3 Back-End-of-Line (BEOL) Layers

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| Layer | Description                | Lithography | Patterning |
|-------|----------------------------|-------------|------------|
| M1    | Metal 1 interconnect layer | EUV         | DPT        |
| V1    | Via connecting M1 to M2    | EUV         | DPT        |
| M2    | Metal 2 interconnect layer | EUV         | DPT        |
| V2    | Via connecting M2 to M3    | EUV         | DPT        |
| M3    | Metal 3 interconnect layer | EUV         | DPT        |
| V3    | Via connecting M3 to M4    | EUV         | DPT        |
| M4    | Metal 4 interconnect layer | EUV         | SPT        |
| V4    | Via connecting M4 to M5    | EUV         | SPT        |

|      |                              |      |     |
|------|------------------------------|------|-----|
| M5   | Metal 5 interconnect layer   | EUV  | SPT |
| V5   | Via connecting M5 to M6      | EUV  | SPT |
| M6   | Metal 6 interconnect layer   | EUV  | SPT |
| V6   | Via connecting M6 to M7      | EUV  | SPT |
| M7   | Metal 7 interconnect layer   | 193i | LE2 |
| V7   | Via connecting M7 to M8      | 193i | LE2 |
| M8   | Metal 8 interconnect layer   | 193i | LE2 |
| V8   | Via connecting M8 to M9      | 193i | LE2 |
| M9   | Metal 9 interconnect layer   | 193i | LE2 |
| V9   | Via connecting M9 to M10     | 193i | LE2 |
| M10  | Metal 10 interconnect layer  | 193i | SE  |
| V10  | Via connecting M10 to M11    | 193i | SE  |
| M11  | Metal 11 interconnect layer  | 193i | SE  |
| V11  | Via connecting M11 to M12    | 193i | SE  |
| M12  | Metal 12 interconnect layer  | 193i | SE  |
| V12  | Via connecting M12 to M13    | 193i | SE  |
| M13  | Metal 13 interconnect layer  | 193i | SE  |
| VRDL | Via connecting M13 to RDL    | 193i | SE  |
| RDL  | Metal RDL interconnect layer | 193i | SE  |

## 2. Physical Design Rules

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### 2.1 Geometry Check

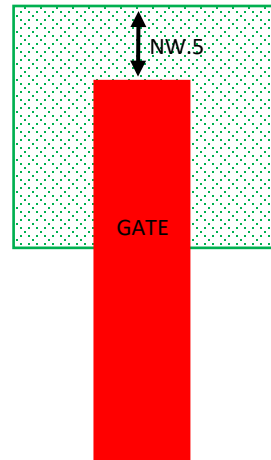
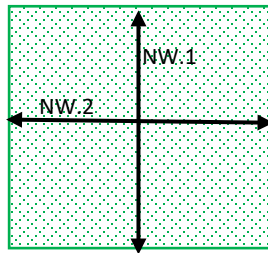
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| Rule | Value | Description                           |
|------|-------|---------------------------------------|
| 1    | -     | Non-orthogonal shapes are not allowed |

### 2.2 N-Well (NW) Rules

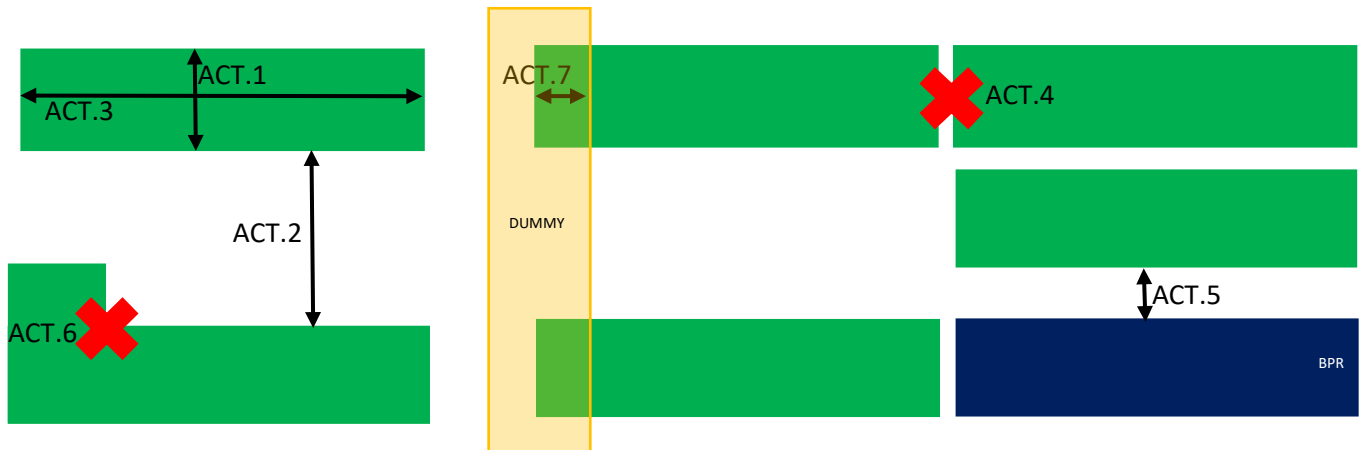
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| Rule | Value                | Description   |
|------|----------------------|---|
| NW.1 | 57.5 nm              | Minimum vertical width of NW                        |
| NW.2 | 84 nm                | Minimum horizontal width of NW                      |
| NW.3 | 6237 nm <sup>2</sup> | Minimum area/enclosed area of NW                    |
| NW.4 | -                    | NW must be orthogonal                               |
| NW.5 | 7 nm                 | Minimum extension of NW past GATE (not cut by GCUT) |



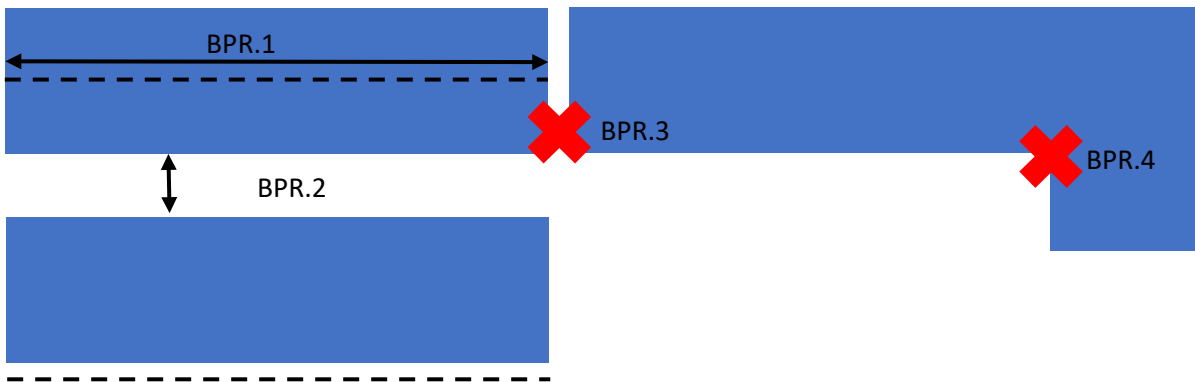
## 2.3 Active (ACT) Rules

| Rule  | Value   | Description                                  |
|-------|---------|--|
| ACT.1 | 21 nm   | Minimum vertical width of ACT                |
| ACT.2 | 21.5 nm | Minimum vertical spacing of ACT              |
| ACT.3 | 84 nm   | Minimum horizontal width of ACT              |
| ACT.4 |         | ACT should be continuous                     |
| ACT.5 | 10 nm   | Minimum vertical spacing between ACT and BPR |
| ACT.6 |         | ACT may not bend                             |
| ACT.7 |         | ACT must end inside DUMMY layer.             |



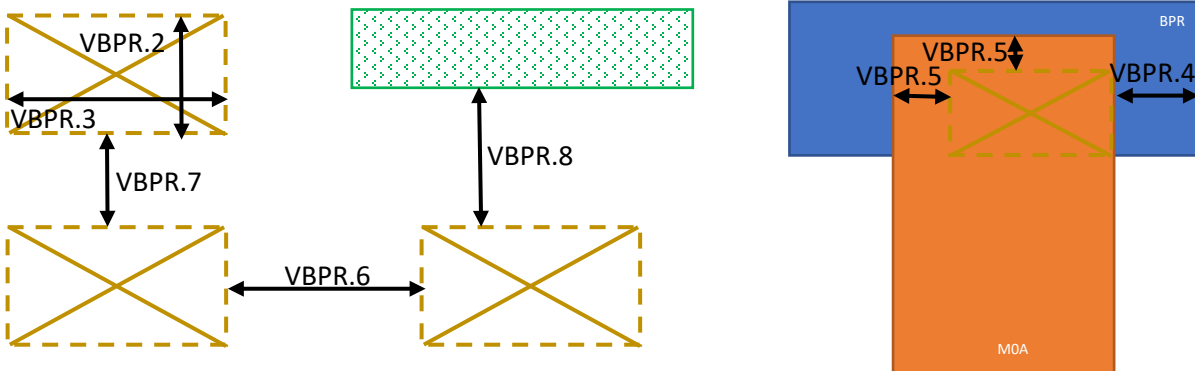
## 2.4 Buried Power Rail (BPR) Rules

| Rule  | Value   | Description                                 |
|-------|---------|---|
| BPR.1 | 31.5 nm | BPR Vertical Width                          |
| BPR.2 | 84 nm   | Minimum vertical spacing between BPR layers |
| BPR.3 |         | BPR must be continuous                      |
| BPR.4 |         | BPR might not bend                          |



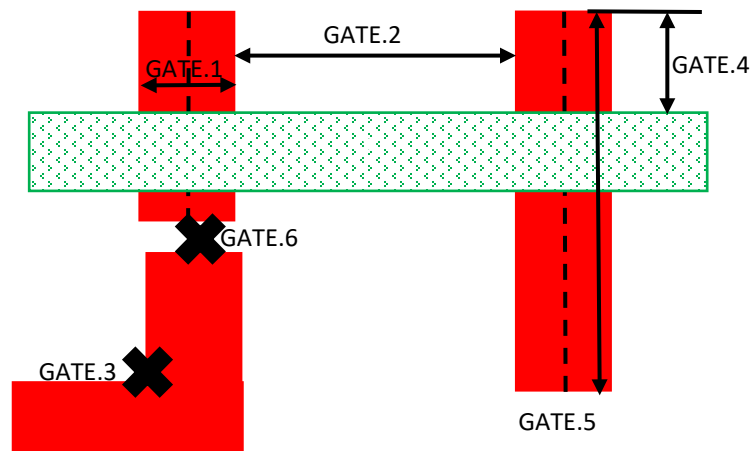
## 2.5 Via Buried Power Rail (VBPR) Rules

| Rule   | Value   | Description  |
|--------|---------|--|
| VBPR.1 |         | VBPR Must be rectangle   |
| VBPR.2 | 10.5 nm | Exact VERTICAL width of VBPR   |
| VBPR.3 | 15 nm   | Exact HORIZONTAL length of VBPR  |
| VBPR.4 | 13.5 nm | VBPR enclosure by BPR on two opposite sides, horizontal direction          |
| VBPR.5 | 0 nm    | VBPR enclosure by M0A on two opposite sides, vertical direction            |
| VBPR.6 | 27 nm   | Minimum horizontal spacing between two VBPR layer                          |
| VBPR.7 | 10 nm   | Minimum vertical spacing between two VBPR layer                            |
| VBPR.8 | 10 nm   | Minimum spacing between VBPR and ACTIVE layer polygons not on the same net |
| VBPR.9 |         | VBPR may not interact with GCUT or GATE or DUMMY                           |



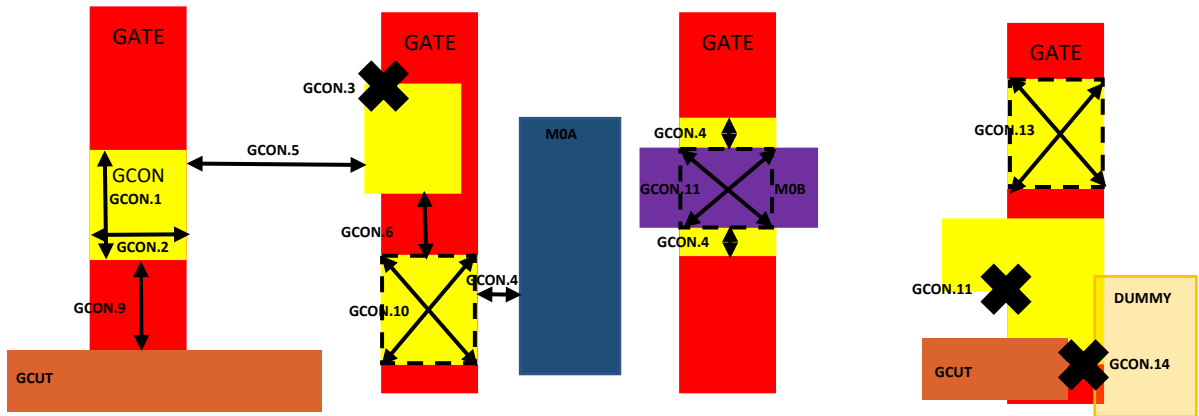
## 2.6 Gate Layer

| Rule   | Value   | Description  |
|--------|---------|--|
| GATE.1 | 15 nm   | GATE exact horizontal width  |
| GATE.2 | 27 nm   | Minimum horizontal spacing between GATE or DUMMY layers  |
| GATE.3 |         | GATE may not bend  |
| GATE.4 | 21.5 nm | GATE min extension past ACT  |
| GATE.5 | 40 nm   | GATE minimum vertical length   |
| GATE.6 |         | GATE may not be discontinuous along the vertical axis. Use GCUT layer to mark cuts in the GATE |
| GATE.7 |         | ACT layer vertical edge may not lie inside, or coincide with, the GATE layer                   |
| GATE.8 | 6 nm    | Minimum horizontal spacing between ACT and GATE (not cut by GCUT and not interacting with ACT) |



## 2.7 Gate Contact (GCON) Layer

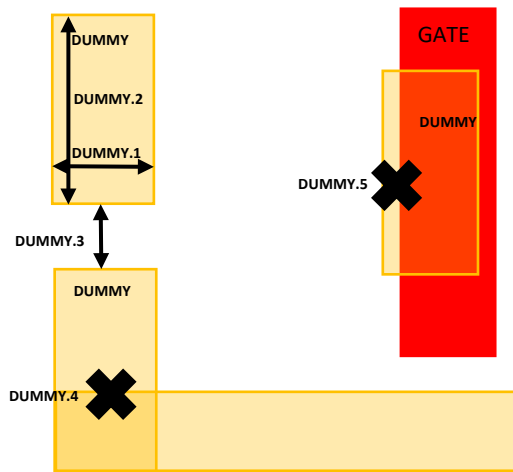
| Rule    | Value               | Description  |
|---------|---------------------|--|
| GCON.1  | 13 nm               | Exact VERTICAL width of GCON                           |
| GCON.2  | 15 nm               | Exact HORIZONTAL length of GCON                        |
| GCON.3  |                     | GCON must overlap gate                                 |
| GCON.4  | 1 nm                | Extension past M0B in vertical direction               |
| GCON.5  | 25 nm               | Minimum horizontal spacing between two GCON layer      |
| GCON.6  | 28 nm               | Minimum vertical spacing between two GCON layer        |
| GCON.7  | 6 nm                | Minimum spacing between GCON and M0A layer polygons    |
| GCON.8  | 25 nm               | Minimum horizontal spacing between GCON and GATE layer |
| GCON.9  | 13.5 nm             | Minimum vertical spacing between GCON and GCUT         |
| GCON.10 | 180 nm <sup>2</sup> | Minimum GCON Area                                      |
| GCON.11 |                     | GCON may not bend                                      |
| GCON.12 | 165 nm <sup>2</sup> | Minimum area of overlap between GCON and M0B           |
| GCON.13 | 180 nm <sup>2</sup> | Minimum area of overlap between GCON and GATE          |
| GCON.14 |                     | GCON may not interact with GCUT or DUMMY               |





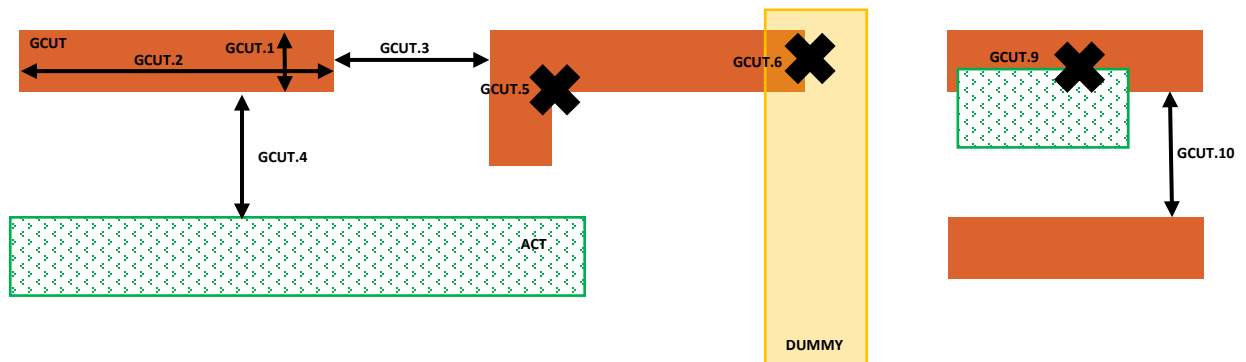
## 2.8 Dummy Layer

| Rule    | Value    | Description                        |
|---------|----------|------------------------------------|
| DUMMY.1 | 15 nm    | DUMMY exact horizontal width       |
| DUMMY.2 | 40 nm    | DUMMY minimum vertical length      |
| DUMMY.3 | 115.5 nm | Minimum vertical space             |
| DUMMY.4 |          | DUMMY may not bend                 |
| DUMMY.5 |          | DUMMY must completely overlap GATE |



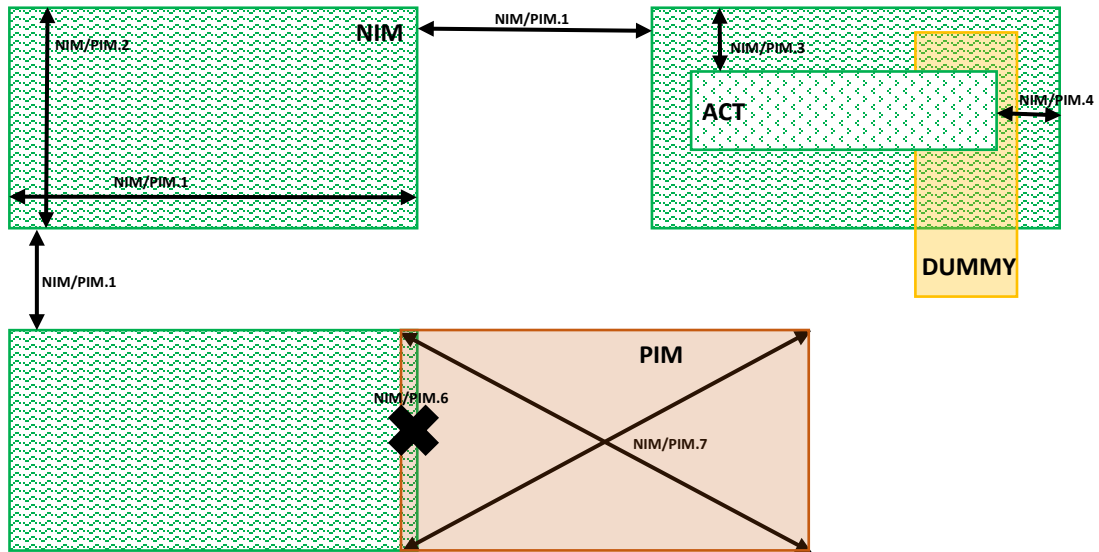
## 2.9 Gate Metal Cut (GCUT) Layer

| Rule    | Value   | Description   |
|---------|---------|---|
| GCUT.1  | 10.5 nm | Exact vertical width of GCUT (shape is oriented horizontally)                 |
| GCUT.2  | 42 nm   | Minimum horizontal length of GCUT(shape is oriented horizontally)             |
| GCUT.3  | 69 nm   | Minimum horizontal space of GCUT  |
| GCUT.4  | 20.5 nm | GCUT minimum space to ACT (must be $20.5 = 10 + 10.5$ //)                     |
| GCUT.5  |         | GCUT may not bend   |
| GCUT.6  |         | GCUT vertical edge must coincide with DUMMY vertical edge                     |
| GCUT.7  |         | GCUT layer may not exist without the layer GATE                               |
| GCUT.8  |         | GCUT layer vertical edge may not lie inside, or coincide with, the GATE layer |
| GCUT.9  |         | GCUT may not interact with ACT  |
| GCUT.10 | 105 nm  | Minimum vertical spacing between two GCUT layer                               |



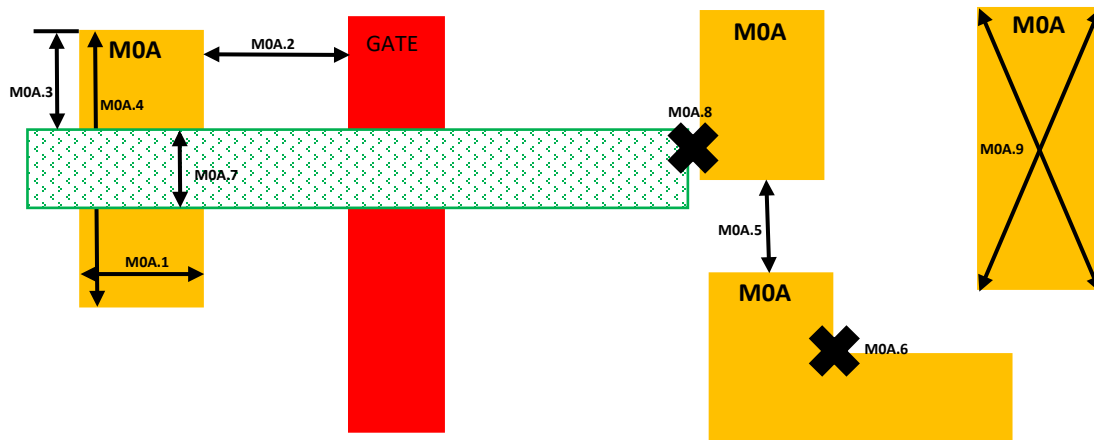
## 2.10 NIM/PIM Layer

| Rule      | Value                | Description   |
|-----------|----------------------|---|
| NIM/PIM.1 | 84 nm                | Minimum width/spacing/notch of NIM/PIM                    |
| NIM/PIM.2 | 57.5 nm              | Minimum vertical width of NIM/PIM                         |
| NIM/PIM.3 | 20 nm                | Minimum enclose of ACT by NIM/PIM on vertical direction   |
| NIM/PIM.4 | 13.5 nm              | Minimum enclose of ACT by NIM/PIM on horizontal direction |
| NIM/PIM.5 | 4830 nm <sup>2</sup> | Minimum NIM/PIM area/enclosed area                        |
| NIM/PIM.6 |                      | NIM and PIM may not overlap                               |



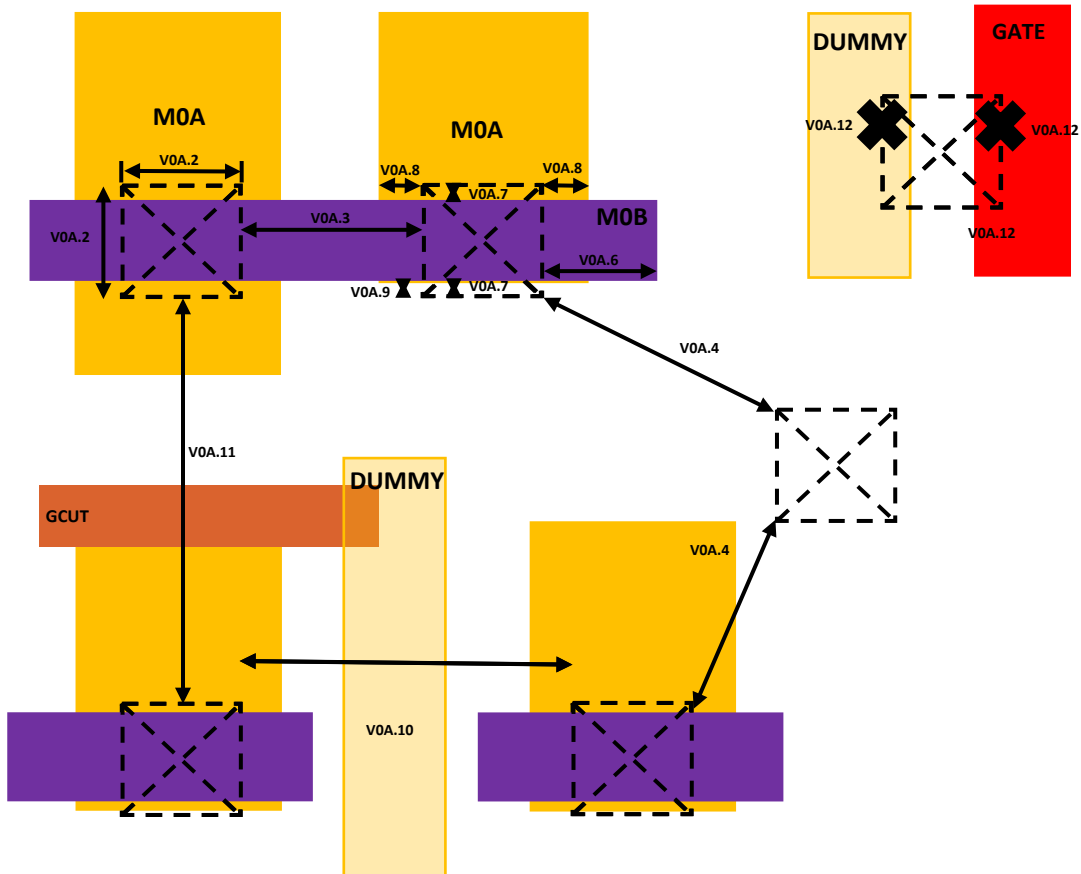
## 2.11 M0A Layer

| Rule  | Value                 | Description  |
|-------|-----------------------|--|
| M0A.1 | 15 nm                 | Minimum width of M0A                                     |
| M0A.2 | 6 nm                  | Minimum spacing of M0A to GATE                           |
| M0A.3 | 5 nm                  | Minimum extension of ACT past M0A (horizontal direction) |
| M0A.4 | 21.5 nm               | Vertical length of M0A                                   |
| M0A.5 | 10 nm                 | Vertical spacing of M0A                                  |
| M0A.6 |                       | M0A may not bend   |
| M0A.7 | 11 nm                 | Minimum vertical overlap between M0A and ACTIVE          |
| M0A.8 |                       | M0A may not be outside ACTIVE                            |
| M0A.9 | 322.5 nm <sup>2</sup> | Minimum M0A area   |



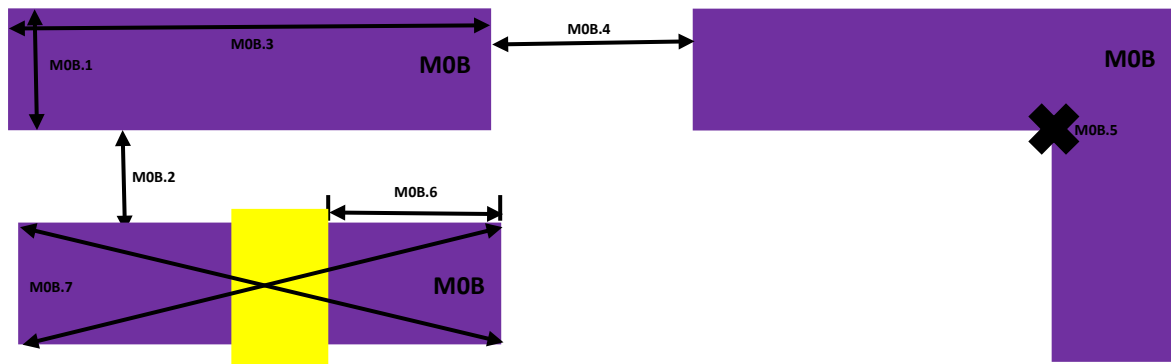
## 2.12 V0A Layer

| Rule   | Value               | Description  |
|--------|---------------------|--|
| V0A.1  |                     | V0A shape is a square  |
| V0A.2  | 13 nm               | V0A is a square with 13nm edge length                            |
| V0A.3  | 29 nm               | Minimum spacing of V0A - Full alignment                          |
| V0A.4  | 30 nm               | Minimum corner-to-corner spacing between two V0A instances       |
| V0A.5  |                     | V0A must always interact with M0A and M0B                        |
| V0A.6  | 6 nm                | V0A enclosure by M0B on two opposite sides, horizontal direction |
| V0A.7  | -1 nm               | V0A enclosure by M0B on two opposite sides, vertical direction   |
| V0A.8  | 1 nm                | V0A enclosure by M0A on two opposite sides, horizontal direction |
| V0A.9  | -1 nm               | V0A enclosure by M0A on opposite sides, vertical direction       |
| V0A.10 | 8 nm                | Minimum space of V0A and M0B of different net                    |
| V0A.11 | 16.5 nm             | Minimum space of V0A and M0A of different net                    |
| V0A.12 |                     | V0A may not interact with DUMMY or GATE layer                    |
| V0A.13 | 156 nm <sup>2</sup> | Minimum area overlap between M0A and V0A                         |



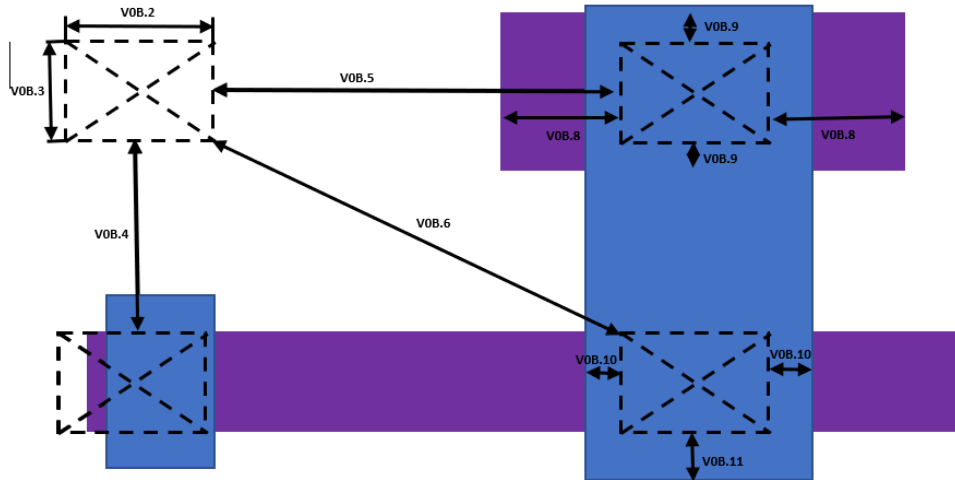
## 2.13 M0B Layer

| Rule  | Value               | Description                        |
|-------|---------------------|------------------------------------|
| M0B.1 | 11 nm               | Minimum Vertical width of M0B      |
| M0B.2 | 10 nm               | Minimum Vertical spacing of M0B    |
| M0B.3 | 22 nm               | Minimum Horizontal width of M0B    |
| M0B.4 | 20 nm               | M0B minimum horizontal spacing     |
| M0B.5 |                     | M0B may not bend                   |
| M0B.6 | 3.5 nm              | Minimum extension of MOB past GCON |
| M0B.7 | 242 nm <sup>2</sup> | Minimum M0B area                   |



## 2.14 V0B Layer

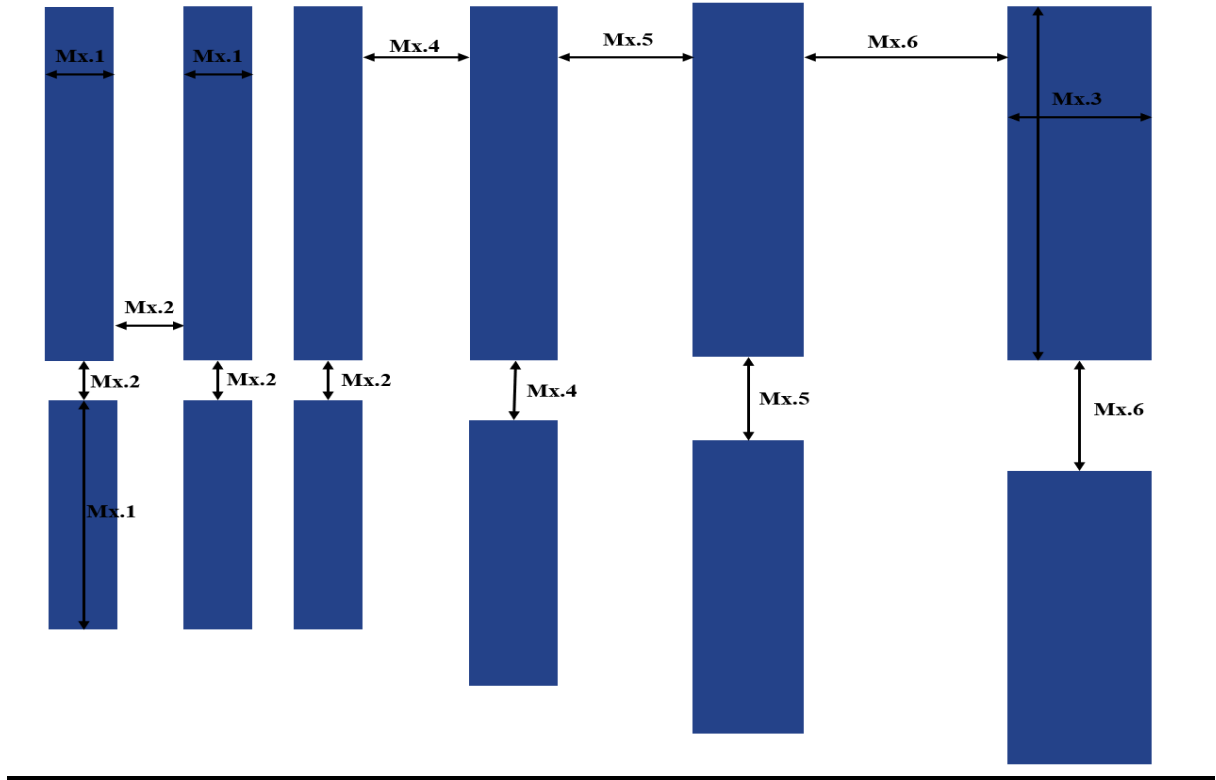
| Rule   | Value   | Description  |
|--------|---------|--|
| V0B.1  |         | V0B shape is a rectangle   |
| V0B.2  | 14 nm   | V0B exact horizontal width                                       |
| V0B.3  | 10 nm   | V0B exact vertical width   |
| V0B.4  | 10.5 nm | Minimum vertical spacing of V0B - Full alignment                 |
| V0B.5  | 20 nm   | Minimum horizontal spacing of V0B - Full alignment               |
| V0B.6  | 22 nm   | Minimum corner-to-corner spacing between two V0B instances       |
| V0B.7  |         | V0B must always interact with M0B and M1                         |
| V0B.8  | 4 nm    | V0B enclosure by M0B on two opposite sides, horizontal direction |
| V0B.9  | 0 nm    | V0B enclosure by M0B on two opposite sides, VERTICAL direction   |
| V0B.10 | 0 nm    | V0B enclosure by M1 on two opposite sides, horizontal direction  |
| V0B.11 | 2.5 nm  | V0B enclosure by M1 on two opposite sides, VERTICAL direction    |



## 2.15 Metalx (Mx) Layers

| Rule                        | Value   | Description   |
|-----------------------------|---------|---|
| Mx.1 <sub>(x=1,2)</sub>     | 14 nm   | METALx width minimum  |
| Mx.1 <sub>(x=3)</sub>       | 15 nm   | METALx width minimum  |
| Mx.1 <sub>(x=4-6)</sub>     | 24 nm   | METALx width minimum  |
| Mx.1 <sub>(x=7-9)</sub>     | 40 nm   | METALx width minimum  |
| Mx.1 <sub>(x=10-11)</sub>   | 80 nm   | METALx width minimum  |
| Mx.1 <sub>(x=12-13)</sub>   | 160 nm  | METALx width minimum  |
| Mx.2 <sub>(x=1-3)</sub>     | 15 nm   | METALx spacing minimum  |
| Mx.2 <sub>(x=4-6)</sub>     | 24 nm   | METALx spacing minimum  |
| Mx.2 <sub>(x=7-9)</sub>     | 40 nm   | METALx spacing minimum  |
| Mx.2 <sub>(x=10-11)</sub>   | 80 nm   | METALx spacing minimum  |
| Mx.2 <sub>(x=12-13)</sub>   | 160 nm  | METALx spacing minimum  |
| Mx.3 <sub>(x=2-3)</sub>     | 750 nm  | METALx maximum width  |
| Mx.3 <sub>(x=4-6)</sub>     | 1200 nm | METALx maximum width  |
| Mx.3 <sub>(x=7-9)</sub>     | 2000 nm | METALx maximum width  |
| Mx.3 <sub>(x=10-11)</sub>   | 4000 nm | METALx maximum width  |
| Mx.3 <sub>(x=12-13)</sub>   | 8000 nm | METALx maximum width  |
| Mx.4 <sub>(x=1-3)</sub>     | 45 nm   | Minimum spacing of METALx wider than 45nm and longer than 45nm                        |
| Mx.4 <sub>(x=4-6)</sub>     | 72 nm   | Minimum spacing of METALx wider than 72nm and longer than 72nm                        |
| Mx.4 <sub>(x=7-9)</sub>     | 120 nm  | Minimum spacing of METALx wider than 120nm and longer than 120nm                      |
| Mx.4 <sub>(x=10-11)</sub>   | 240 nm  | Minimum spacing of METALx wider than 240nm and longer than 240nm                      |
| Mx.4 <sub>(x=12-13)</sub>   | 480 nm  | Minimum spacing of METALx wider than 480nm and longer than 480nm                      |
| Mx.5 <sub>(x=1-3)</sub>     | 135 nm  | Minimum spacing of METALx wider than 135nm and longer than 135nm                      |
| Mx.5 <sub>(x=4-6)</sub>     | 216 nm  | Minimum spacing of METALx wider than 216nm and longer than 216nm                      |
| Mx.5 <sub>(x=7-9)</sub>     | 360 nm  | Minimum spacing of METALx wider than 360nm and longer than 360nm                      |
| Mx.5 <sub>(x=10-11)</sub>   | 720 nm  | Minimum spacing of METALx wider than 720nm and longer than 720nm                      |
| Mx.5 <sub>(x=12-13)</sub>   | 1440 nm | Minimum spacing of METALx wider than 1440nm and longer than 1440nm                    |
| Mx.6 <sub>(x=1-3)</sub>     | 405 nm  | Minimum spacing of METALx wider than 405nm and longer than 405nm                      |
| Mx.6 <sub>(x=4-6)</sub>     | 648 nm  | Minimum spacing of METALx wider than 648nm and longer than 648nm                      |
| Mx.6 <sub>(x=7-9)</sub>     | 1080 nm | Minimum spacing of METALx wider than 1080nm and longer than 1080nm                    |
| Mx.6 <sub>(x=10-11)</sub>   | 2160 nm | Minimum spacing of METALx wider than 2160nm and longer than 2160nm                    |
| Mx.6 <sub>(x=12-13)</sub>   | 4320 nm | Minimum spacing of METALx wider than 4320nm and longer than 4320nm                    |
| Mx.7 <sub>(x=1-3,7-9)</sub> |         | Double patterning Error   |
| Mx.8 <sub>(x=1-3,7-9)</sub> |         | Density Balancing Rule: The density of decomposed metals should be between 23 and 77% |

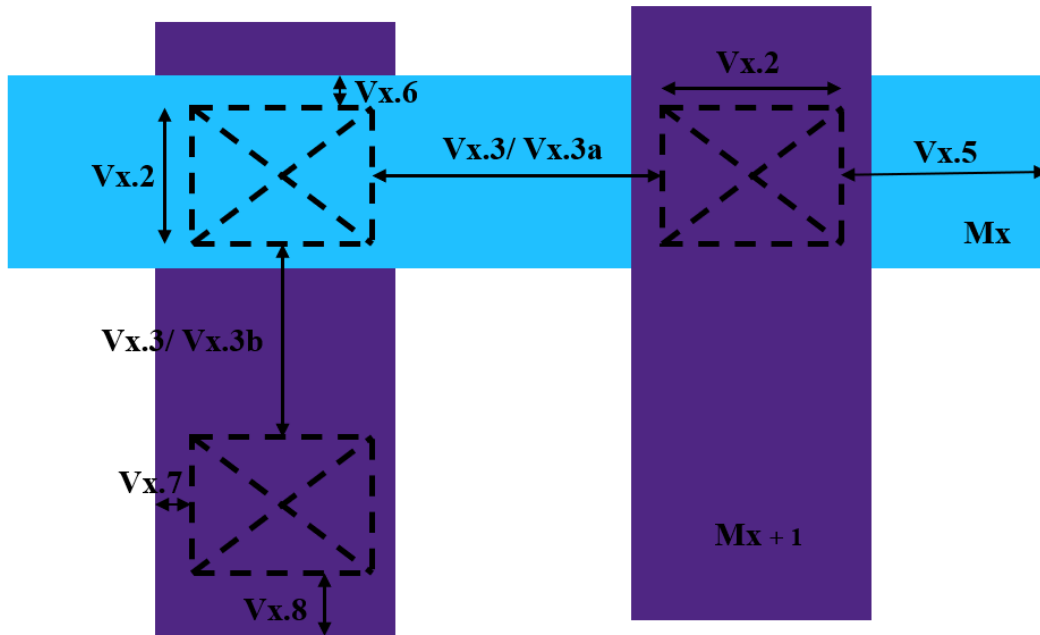




## 2.16 ViaX (Vx) Layers

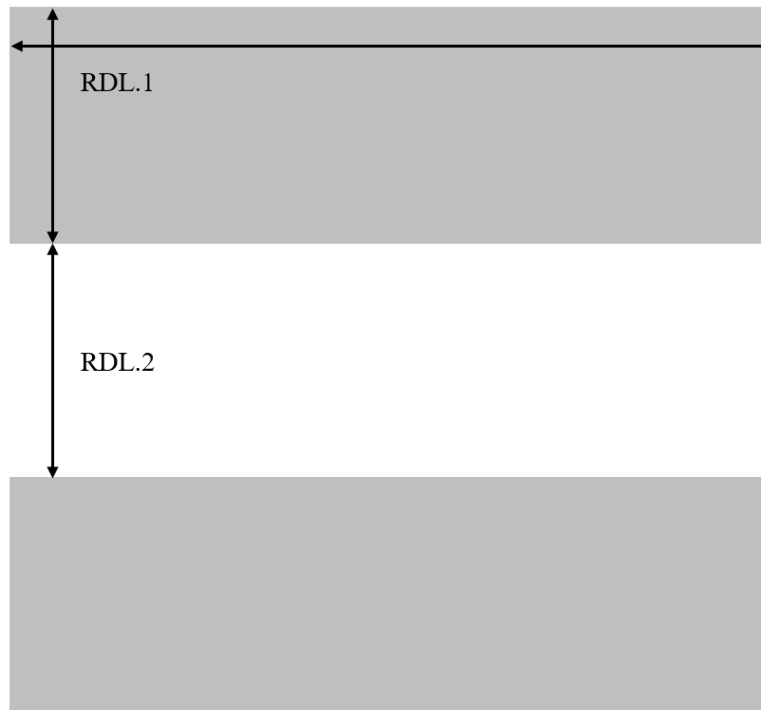
| Rule                                | Value      | Description   |
|-------------------------------------|------------|---|
| Vx.1 (x=1,2,<br>4,5,7,8,10,12,VRDL) |            | Vx shape is square  |
| Vx.1 (x=3,6,9,11)                   |            | Vx shape is rectangle   |
| Vx.2 (x=1,2)                        | 14 nm      | Vx is a square with 14nm edge length  |
| Vx.2 (x=3)                          | 15, 24 nm  | Vx is a rectangle with 15nm horizontal edge and 24nm vertical edge            |
| Vx.2 (x=4,5)                        | 24 nm      | Vx is a square with 24nm edge length  |
| Vx.2 (x=6)                          | 40,24 nm   | Vx is a rectangle with 40nm horizontal edge and 24nm vertical edge            |
| Vx.2 (x=7,8)                        | 40 nm      | Vx is a square with 40nm edge length  |
| Vx.2 (x=9)                          | 40,80 nm   | V9 is a rectangle with 40nm horizontal edge and 80nm vertical edge            |
| Vx.2 (x=10)                         | 80nm       | V10 is a square with 80nm edge length   |
| Vx.2 (x=11)                         | 80, 160 nm | V11 is a rectangle with 80nm horizontal edge and 160nm vertical edge          |
| Vx.2 (x=12,VRDL)                    | 160 nm     | V12 is a square with 160nm edge length  |
| Vx.3 (x=1,2)                        | 14 nm      | Minimum spacing of Vx - Full alignment  |
| Vx.3a (x=3)                         | 15 nm      | Minimum horizontal spacing of Vx - Full alignment                             |
| Vx.3b (x=3)                         | 24 nm      | Minimum vertical spacing of Vx - Full alignment                               |
| Vx.3 (x=4,5)                        | 24 nm      | Minimum spacing of Vx - Full alignment  |
| Vx.3a (x=6)                         | 40 nm      | Minimum horizontal spacing of Vx - Full alignment                             |
| Vx.3b (x=6)                         | 24 nm      | Minimum vertical spacing of Vx - Full alignment                               |
| Vx.3 (x=7,8)                        | 40 nm      | Minimum spacing of Vx - Full alignment  |
| Vx.3a (x=9)                         | 40 nm      | Minimum horizontal spacing of Vx - Full alignment                             |
| Vx.3b (x=9)                         | 80 nm      | Minimum vertical spacing of V9 - Full alignment                               |
| Vx.3 (x=10)                         | 80 nm      | Minimum spacing of V10 - Full alignment                                       |
| Vx.3a (x=11)                        | 80 nm      | Minimum horizontal spacing of V11 - Full alignment                            |
| Vx.3b (x=11)                        | 160 nm     | Minimum vertical spacing of V11 - Full alignment                              |
| Vx.3 (x=12,VRDL)                    | 160 nm     | Minimum spacing of V12 - Full alignment                                       |
| Vx.4 (x=1-12)                       |            | V <sub>x</sub> should be enclosed between M <sub>x</sub> and M <sub>x+1</sub> |
| Vx.4 (x=VRDL)                       |            | V <sub>x</sub> should be enclosed between M13 and RDL                         |
| Vx.5<br>(x=1,3,5,7,9,11,VRDL)       | 0 nm       | Vx enclosure by M <sub>x</sub> on two opposite sides, horizontal direction    |
| Vx.5 (x=2)                          | 3 nm       | Vx enclosure by M <sub>x</sub> on two opposite sides, horizontal direction    |
| Vx.5<br>(x=4,6,8,10,12)             | 10 nm      | Vx enclosure by M <sub>x</sub> on two opposite sides, horizontal direction    |
| Vx.6 (x=1,3)                        | 3 nm       | Vx enclosure by M <sub>x</sub> on two opposite sides, vertical direction      |
| Vx.6<br>(x=2,4,6,8,10,12)           | 0 nm       | Vx enclosure by M <sub>x</sub> on two opposite sides, vertical direction      |
| Vx.6<br>(x=5,7,9,11,VRDL)           | 10 nm      | Vx enclosure by M <sub>x</sub> on two opposite sides, vertical direction      |
| Vx.7 (x=1,3)                        | 3 nm       | Vx enclosure by M <sub>x+1</sub> on two opposite sides, horizontal direction  |
| Vx.7<br>(x=2,4,6,8,10,12)           | 0 nm       | Vx enclosure by M <sub>x+1</sub> on two opposite sides, horizontal direction  |
| Vx.7 (x=5,7,9,11)                   | 10 nm      | Vx enclosure by M <sub>x+1</sub> on two opposite sides, horizontal direction  |
| Vx.7 (x=VRDL)                       | 80 nm      | VRDL enclosure by RDL in horizontal direction                                 |
| Vx.8<br>(x=1,3,5,7,9,11)            | 0 nm       | Vx enclosure by M <sub>x+1</sub> on two opposite sides, vertical direction    |
| Vx.8 (x=2)                          | 3 nm       | Vx enclosure by M <sub>x+1</sub> on two opposite sides, vertical direction    |
| Vx.8<br>(x=4,6,8,10,12)             | 10 nm      | Vx enclosure by M <sub>x+1</sub> on two opposite sides, vertical direction    |

|                      |                       |  |
|----------------------|-----------------------|--|
| $Vx.8_{(x=VRDL)}$    | 80 nm                 | VRDL enclosure by RDL in vertical direction  |
| $Vx.9_{(x=1,2)}$     | 196 nm <sup>2</sup>   | Minimum area overlap between $Mx$ and $Vx$   |
| $Vx.9_{(x=3)}$       | 360 nm <sup>2</sup>   | Minimum area overlap between $Mx$ and $Vx$   |
| $Vx.9_{(x=4,5)}$     | 576 nm <sup>2</sup>   | Minimum area overlap between $Mx$ and $Vx$   |
| $Vx.9_{(x=6)}$       | 960 nm <sup>2</sup>   | Minimum area overlap between $Mx$ and $Vx$   |
| $Vx.9_{(x=7,8)}$     | 1600 nm <sup>2</sup>  | Minimum area overlap between $M7$ and $V7$   |
| $Vx.9_{(x=9)}$       | 3200 nm <sup>2</sup>  | Minimum area overlap between $M9$ and $V9$   |
| $Vx.9_{(x=10)}$      | 6400 nm <sup>2</sup>  | Minimum area overlap between $M10$ and $V10$ |
| $Vx.9_{(x=11)}$      | 12800 nm <sup>2</sup> | Minimum area overlap between $M11$ and $V11$ |
| $Vx.9_{(x=12,VRDL)}$ | 25600 nm <sup>2</sup> | Minimum area overlap between $M12$ and $V12$ |



## 2.17 RDL Layer

| Rule  | Value             | Description         |
|-------|-------------------|---------------------|
| RDL.1 | 1.6 $\mu\text{m}$ | RDL width minimum   |
| RDL.2 | 1.6 $\mu\text{m}$ | RDL spacing minimum |



## 2.18 Other Rules

| Rule    | Value  | Description   |
|---------|--------|---|
| GRID    | 0.5 nm | Shapes on all layers must be on a 0.5 nm grid                               |
| ANTENNA | 50:1   | Ratio of Maximum Allowed (GATE or Metal Layer Area) to transistor Gate Area |